

Substitute for Form 1449A/PTO (Modified) (use as many sheets as necessary)		Attorney Docket No.: 42390P11369	Application Number: Not Yet Assigned
		First Named Inventor: Chen et al.	
		Filing Date: Concurrently Herewith	

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		WARREN GROBMAN AND YAO-TING WANG. Practical IC Design in the Subwavelength Regime. Web Page [online]. Integrated System Design Magazine. Posted 01/30/01. [Retrieved on May 25, 2001] Retrieved on the Internet: <URL: http://www.isdmag.com/story/OEG20010130S0098 . Pages 1-8.	
		Integrated System Design Magazine - isdmag.com. Figures 1-4. Web Page [online]. [Retrieved on May 25, 2001] Retrieved on the Internet: <URL: http://www.isdmag.com/editorial/2001/coverstory/figures0102.html . Pages 1-4.	
		DR. J. TRACY WEED and DR. LINARD KARL LIN. Dark-Field Double Exposure PSM Technique: A Manufacturing Approach to Phase Shifting. Semiconductors: SubMicron Focus: Double Exposure. Web Page [online]. Canon U.S.A. Inc. [Retrieved on May 29, 2001] Retrieved on the Internet: <URL: http://www.usa.canon.com/indtech/semicondeq/news_springs51_4.html . Pages 1-9.	
		KENJI SAITO, MASANOBU HASEGAWA, AKIYOSHI SUZUKI and MINORU YOSHII. IDEAL Way to Extend Optical Lithography. Semiconductors: SubMicron Focus: Aberrations. Web Page [online]. Canon U.S.A. Inc. [Retrieved on May 29, 2001] Retrieved on the Internet: <URL: http://www.usa.canon.com/indtech/semicondeq/news_ideal.html . Pages 1-9.	
		STAN CHOW, ANDREW B. KAHNG AND MAJID SARRAFZADEH. Modern Physical Design: Algorithm Technology Methodology (Part V). ICCAD Tutorial, November 9, 2000. [online] [Retrieved on June 22, 2001] Retrieved on the Internet: <URL: http://www.vlsicad.cs.ucla.edu/ICCAD00TUTORIAL/part5.pdf . Pages 1- 44.	
Examiner Signature			Date Considered <u>2/11/04</u>

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